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Reply to Office action of September 21, 2004

Amendments to the Claims:

This listing of claims reflects all claim amendments and replaces all prior

versions, and listings, of claims in the application (material to be inserted is in bold and

underline, and material to be deleted is in strikeout or (if the deletion is of five or fewer

consecutive characters or would be difficult to see) in double brackets [[]].

<u>Listing of Claims:</u>

1-35. (cancelled)

36. (currently amended) A vapor deposition effusion system, comprising:

a device configured to translate a strip material through a deposition zone and

along a processing path, each of the strip material and the deposition zone having a

width oriented perpendicular to the processing path and a length oriented parallel to the

processing path; and

first and second substantially closed vessels located serially along the

processing path, each vessel containing a heated quantity of a different source material,

the first and second vessels being configured to concurrently emit the different

source materials and produce overlapping plumes of the different source materials in

the deposition zone, each vessel including an array of vapor delivery nozzles distributed

uniformly across the vessel in a direction corresponding to the width of the deposition

zone and configured to expel overlapping plumes of source material, so that a fog of

source materials is created and deposited on the strip material in the deposition zone,

the fog having a substantially uniform composition across the width of the deposition

zone and a varying composition across the length of the deposition zone.

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37. (previously presented) The system of claim 36, further comprising

a heating system adapted to maintain the nozzle at a temperature higher than

the source material.

(previously presented) The system of claim 36, further comprising 38.

at least a third substantially closed vessel located serially relative to the first and

second vessels along the processing path in the deposition zone, the third vessel

containing a different composition than the first and second vessels.

39. The system of claim 36, wherein the source (previously presented)

materials are selected from the group comprising copper, gallium, and indium.

40. (previously presented) The system of claim 36 further comprising a

thermal control shield disposed at least partially around the vessel.

41. (previously presented) The system of claim 40, wherein the thermal

control shield includes an outer shell and plural insulation layers.

42. (previously presented) The system of claim 41, wherein the outer shell is

formed of one or more materials chosen from the following group: graphite, boron

nitride, tantalum, molybdenum, tungsten, rhenium and titanium.

43. (previously presented) The system of claim 41, wherein the outer shell is

ceramic coated.

The system of claim 36, wherein the vessel 44. (previously presented)

includes plural spaced-apart vapor delivery nozzles.

45. (previously presented) The system of claim 41, wherein the nozzles are

disposed along an elongate axis configured to expel overlapping plumes of source

material, whereby a fog of source material of substantially uniform flux along the

elongate axis is created.

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46. (previously presented) The system of claim 41, wherein the vessel is constructed of materials chosen from the group consisting of graphite, pyrolitic boron nitride coated graphite, tantalum, molybdenum, tungsten and ceramics.

47. (previously presented) The system of claim 36, wherein the vessel includes a crucible and a lid, wherein the at least one vapor delivery nozzle is positioned in the lid.

48. (previously presented) The system of claim 47, wherein the at least one nozzle is integrally formed into the lid.

49. (previously presented) The system of claim 47, wherein there are plural nozzles positioned on the lid.

50. (previously presented) The system of claim 49, wherein the nozzles are spaced apart between 1 and 20 centimeters.

51. (previously presented) The system of claim 47, wherein the heating system includes an electrical heating element disposed in the lid.

52. (previously presented) The system of claim 51, wherein the heating element disposed in the lid is generally U-shaped.

53. (previously presented) The system of claim 47, wherein the heating system is adapted to maintain the lid at a temperature higher than the source material.

54. (previously presented) The system of claim 36, wherein the at least one nozzle has a discharge opening between 0.25 and 2.5 centimeters in diameter.

55. (previously presented) The system of claim 36, wherein the heating system includes at least one U-shaped heating element.

56. (currently amended) A vapor deposition system, comprising:

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a roll assembly configured to translate a strip material through a deposition zone

and along a processing path, each of the strip material and the deposition zone having

a width oriented perpendicular to the processing path, and a length oriented parallel to

the processing path;

first and second crucibles arranged serially along the processing path to

concurrently emit a different source material and produce overlapping plumes of

different source materials, each crucible having a lid;

each crucible having at least one nozzle in the lid to pass vapor evaporated from

molten source material contained in the crucible; and

each crucible having a source material heating system to control the temperature

of the source material at a desired temperature range;

wherein the roll assembly is configured to maintain a substantially constant travel

speed of the strip material through the deposition zone in relation to the temperature of

source material in the crucible, such that source material of substantially uniform flux is

created and deposited on the strip material.

57. (previously presented) The system of claim 56 further comprising a

nozzle heating system adapted to maintain the nozzle at a temperature above the

temperature of the constituent material.

58. (previously presented) The system of claim 57, wherein the nozzle

heating system is configured to maintain the lid at a temperature above the temperature

of the constituent material.

59. (previously presented) The system of claim 56, wherein in the nozzle is

sized to constitute the rate limiting factor in effusion of the vapor.

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60. (previously presented) The system of claim 56, wherein the nozzle has an opening area between 0.05 and 5 square centimeters.

61. (previously presented) The system of claim 56 further comprising a thermal control shield at least partially surrounding the crucible.

62. (previously presented) The system of claim 61, wherein the thermal control shield includes an outer shell and thermal insulation.

63. (previously presented) The system of claim 56, wherein the crucible is constructed from materials chosen from the following group: graphite, pyrolitic boron nitride coated graphite, tantalum, molybdenum, tungsten and ceramics.

64. (previously presented) The system of claim 36, wherein the device configured to continuously translate a strip material through a deposition zone and along a processing path.

65. (previously presented) The system of claim 36, wherein the strip material is a flexible strip material.

66. (previously presented) The system of claim 65, wherein the device is further configured to translate the flexible strip material to and from rolls of strip material.